Etching Basics

1. Anisotropy -
   a) Isotopic Etching (most wet etches)

   \[ d_f = d + 2h \]
   Define: \( B = d - d_f \)

   If \( B = 2h \) \( \rightarrow \) isotropic

2. Selectivity -

   Only poly-Si etched (no etching of PR or SiO_2)

   PR partially etched

   SiO_2 partially etched after some overetch of the polysilicon